

JC4/92D

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1100 U.S.	512
09 05172	7/13/99
Subclass	
Class	
ISSUE CLASSIFICATION	

PATENT NUMBER

## U.S. UTILITY Patent Application

O.I.P.E. SCANNED	PATENT DATE IKI Q.A. DM
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APPLICATION NO. 09/905172	CONT/PRIOR D.	CLASS 438	SUBCLASS 710	ART UNIT 1765	EXAMINER A. Beck	
APPLICANTS David Mui Wei Liu Thorsten Lill Christopher Bencher						
Etch pattern definition using a CVD organic layer as an anti-reflection coating and hardmask						
TITLE						PTO-2040 12/99

ISSUING CLASSIFICATION					
ORIGINAL		CROSS REFERENCE(S)			
CLASS	SUBCLASS	CLASS	SUBCLASS (ONE SUBCLASS PER BLOCK)		
INTERNATIONAL CLASSIFICATION					
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TERMINAL DISCLAIMER	DRAWINGS			CLAIMS ALLOWED	
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims	Print Claim for O.G.
<input type="checkbox"/> The term of this patent subsequent to _____ (date) has been disclaimed.	(Assistant Examiner) (Date)			NOTICE OF ALLOWANCE MAILED	
<input type="checkbox"/> The term of this patent shall not extend beyond the expiration date of U.S. Patent No. _____				ISSUE FEE	
<input type="checkbox"/> The terminal _____ months of this patent have been disclaimed.	(Primary Examiner) (Date) (Legal Instruments Examiner) (Date)			Amount Due Date Paid	
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